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Notice of Allowability	Application No.	Applicant(s)	
	10/713,036	HAGIWARA ET AL.	
	Examiner	Art Unit	
	John S. Chu	1752	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS In the herewith (or previously mailed), a Notice of Allowance (PTOL-8: NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3	S (OR REMAINS) CLOSED in 5) or other appropriate commu RIGHTS. This application is s	this application. If not included	THIS initiative
1. This communication is responsive to <u>5/9/06</u> .			
2. Mare 10-13,17 and 19-43.			
 Acknowledgment is made of a claim for foreign priority a All b) ☐ Some* c) ☐ None of the: 	under 35 U.S.C. § 119(a)-(d) o	or (f).	
Certified copies of the priority documents have			
2. Certified copies of the priority documents have			
3. Copies of the certified copies of the priority d	ocuments have been received	in this national stage application from	n the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	" of this communication to file MENT of this application.	a reply complying with the requirement	nts
4. A SUBSTITUTE OATH OR DECLARATION must be sub- INFORMAL PATENT APPLICATION (PTO-152) which gi	mitted. Note the attached EXAves reason(s) why the oath or	MINER'S AMENDMENT or NOTICE (declaration is deficient.	OF
5. \square CORRECTED DRAWINGS (as "replacement sheets") mi	ust be submitted.		
(a) ☐ including changes required by the Notice of Draftspe	rson's Patent Drawing Review	(PTO-948) attached	
1) 🗌 hereto or 2) 📗 to Paper No./Mail Date			
(b) including changes required by the attached Examine Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on the header according to 37 CF	e drawings in the front (not the back) of R 1.121(d).	F
 DEPOSIT OF and/or INFORMATION about the dep attached Examiner's comment regarding REQUIREMENT 	osit of BIOLOGICAL MATE FOR THE DEPOSIT OF BIO	ERIAL must be submitted. Note the DLOGICAL MATERIAL.	
Attachment(s)			
1. Notice of References Cited (PTO-892)		ormal Patent Application (PTO-152)	
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)		ımmary (PTO-413), Mail Date	
 Information Disclosure Statements (PTO-1449 or PTO/SB. Paper No./Mail Date 		Amendment/Comment	
raper No./Mail Date	8. 🛛 Examiner's	Statement of Reasons for Allowance	
 Examiner's Comment Regarding Requirement for Deposit of Biological Material 	9. 🗌 Other		

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REASONS FOR ALLOWANCE

1. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following;

10. (Previously presented) A photosensitive resin composition which comprises (1) a polyimide precursor produced using an oxydiphthalic acid or acid anhydride thereof and at least one diamine as reactants for forming the polyimide precursor, wherein said at least one dlamine consists of at least one dlamine selected from the group consisting of diaminodiphenyl ether, diaminodiphenyl sulfone, metaphenylene diamine, p-phenylenediamine, p-xylylenediamine, diaminonaphthalene, dimethylbenzidine, dimethoxylbenzidine, diaminodiphenylmethane, diaminodiphenylsulfide, benzophenonediamine, bis{(aminophenoxy) phenyl}sulfone, hexafluoro-bls(aminophenyl)propane, bis{(aminophenoxy)phenyl}propane, dimethyl-diaminophenyl-methane, tetramethyldiaminodiphenylmethane, bis{(amlnophenoxy)phenyl} sulfone, bis(aminophenyl)propane and diaminopolyslloxane, (2) an addition-polymerizable compound, and (3) a photoinitiator, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light, the polyimide precursor being such that a 20 µm thick film thereof has a transmittance, at 365nm, of at least 40%.

The inventive step is the recited polyimide precursor produced by the oxyphthalic acid or acid anhydride and at least one diamine selected from the group consisting of the listed diamines in claim 10. The current rejection over RIEDIKER et al is withdrawn in view of the comparative evidence that is in the specification wherein the polyamic acid esters made from

pyromellitic acid anhydride as seen in Comparative examples 1 and 2 of TABLE 2 show inferior film remaining ratio of 65% and 58% as compared to the inventive composition showing 94% to 98%. In addition, the compositions with the polyamic acid pyromellitic acid anhydride fail to meet the claimed transmittance as claimed for the 20 µm thick film a 365 nm.

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Newly cited reference to SIMMONS, III (5,399,655) discloses positive working compositions comprising polyamic acid polymers having acid labile groups. The reference lacks the claimed addition-polymerizable compound and photoinitiator in the composition. Likewise, TUNNEY et al (5,122,436) lacks the use of an oxyphthalic dianhydride compound in a working example and any comparative evidence as seen in the specification would overcome a prima facie case of obviousness.

Based on the comparative evidence of record in the specification, any prima facie case of obviousness is overcome and accordingly RIEDIKER et al is withdrawn and claims 3, 4, 10-13, 17 and 19-43 are seen as allowable and passed to issue.

2. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Cynthia Kelly, can be reached on (571) 272-1526

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The fax phone number for the USPTO is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

hn S. Chu rimary Examiner, Group 1700

J.Chu July 19, 2006